



The Materials Metrology™ Company

Press Release

ReVera Announces zMAX™ Depth Distribution Technology for its RVX™ 1000 Compositional Metrology Tool

Non-Destructive Measurement Technology Speeds Introduction of Next Generation Transistors

Sunnyvale, Calif., July 6, 2005 – ReVera Incorporated, the leading provider of compositional metrology solutions for semiconductor manufacturing, announces the availability of its new zMAX™ elemental depth distribution technology for the RVX™ 1000 Compositional Metrology Tool.

By extending the capabilities of ReVera's highly successful RVX 1000 metrology product, customers are able to control the variations that occur inside a film as well as the variations across a film. With this extra dimension of metrology, the RVX 1000 now enables complete composition control of critical films in 65nm and 45nm process development and manufacturing.

David Ring, President and CEO of ReVera, stated: "The performance and yield of today's transistors depends critically on controlling the composition variation inherent to the new processes and materials used in manufacturing. ReVera's RVX 1000 metrology system has been widely adopted by many leading edge semiconductor customers because it solves this critical need."

Continuing, Ring commented: "To enable the next generation of device performance, our customers are now enhancing these transistor film structures by engineering the composition through the depth of the films. For development and manufacturing, they have a significant challenge verifying and controlling variations in film composition from the top of the film to the bottom. zMAX technology for the RVX 1000 solves this critical need."

Designed for use in a production environment, ReVera's proprietary zMAX technology integrates seamlessly into the flexible, recipe configurable RVX 1000 metrology system.

ReVera will highlight its zMAX depth distribution technology at the upcoming SEMICON West show in San Francisco, July 12-14, 2005. Visit ReVera at Booth # 4218 and "Ask Us About zMAX!"